

WEST Search History

DATE: Thursday, October 10, 2002

<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
		result set	
<i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L22	L21 same (shak\$3 or agitat\$5)	187	L22
L21	((photoresist or coat3\$ or wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same (soak\$3 or pre-soak\$3 or dip\$3)	7106	L21
L20	L19 same (shak\$3 or agitat\$5)	9	L20
L19	(photoresist or coat3\$)with (clean\$3 or rins\$3 or remov\$3 or treat\$3) with (soak\$3 or presoak\$3 or dip\$3)	419	L19
L18	L11 same (shak\$3 or agitat\$5)	31	L18
L17	L8 same (shak\$3 or agitat\$5)	75	L17
L16	L15 and agitat\$5	13	L16
L15	l8 and DMSO	35	L15
L14	l8 and (DMSO with TMAH)	0	L14
L13	l8 same (DMSO with TMAH)	0	L13
L12	L11 same DMSO	5	L12
L11	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with soak\$3	976	L11
L10	((wafer or substrate) adj\$3 (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with soak\$3	0	L10
L9	l8 same (reciprocate\$3 or up and down)	14	L9
L8	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same soak\$3	1666	L8
L7	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with soak\$3	0	L7
L6	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with ((vat or tank or liquid) with heat\$3 with (electric\$3 or conduct\$3 or wire))	173	L6
L5	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with heat\$3 with (electric\$3 or conduct\$3 or wire))	239	L5
L4	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with (heat\$3 adj5 wire))	3	L4
L3	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with (heat\$3 adj5 electric\$3))	24	L3
L2	((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with (heat\$3 adj5 electric))	9	L2
<i>DB=USPT,JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ</i>			
L1	(wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3) with (vat or tank or liquid) with (heat\$3 adj3 electric)	3	L1